L Number	Hits	Search Text	DB	Time stamp
-	2	(("20030003407") or ("20030003683")).PN.	USPAT;	2003/01/25 17:17
	25384	(magical on whaterwarish are shottened) A73	US-PGPUB	
-	25384	<pre>(resist or photoresist or photopolymer\$7) near3 (develop\$3)</pre>	USPAT;	2003/01/31 17:10
		nears (developes)	US-PGPUB; EPO; JPO;	
			IBM TDB	
-	1494	((resist or photoresist or photopolymer\$7)	USPAT;	2003/01/31 12:06
		near3 (develop\$3)) with (ultraviolet or	US-PGPUB;	,
		uv)	EPO; JPO;	
	38757	(Ci om cilican en cilican) cità (	IBM_TDB	
-	30737	(Si or silicon or silicone) with (cross adj link\$3 or cur\$3 or harden\$3)	USPAT; US-PGPUB;	2003/01/31 12:07
		adj IImiyo of Garyo of Marachyoy	EPO; JPO;	
Ì			IBM TDB	
-	58	(((resist or photoresist or	USPAT;	2003/01/31 12:07
		photopolymer\$7) near3 (develop\$3)) with	US-PGPUB;	
		(ultraviolet or uv)) and ((Si or silicon	EPO; JPO;	
		or silicone) with (cross adj link\$3 or cur\$3 or harden\$3))	IBM_TDB	
-	391	(ultraviolet or uv) with (neon)	USPAT;	2003/02/15 10:10
		(42324720200 02 01) 11211 (110011)	US-PGPUB;	2003/02/13 10:10
			EPO; JPO;	
			IBM_TDB	
_	57	((ultraviolet or uv) with (neon)) and	USPAT;	2003/02/15 10:11
		((cross adj link\$3 or cur\$3 or harden\$3) with (polymer\$7 or photopolymer\$7 or	US-PGPUB;	
		photoresist or resist))	EPO; JPO; IBM TDB	
-	2	(((ultraviolet or uv) with (neon)) and	USPAT;	2004/01/09 16:54
		((cross adj link\$3 or cur\$3 or harden\$3)	US-PGPUB;	2001/01/03 10:34
	:	with (polymer\$7 or photopolymer\$7 or	EPO; JPO;	
		photoresist or resist))) and (neon same	IBM_TDB	
_	203	<pre>(flow or flowrate)) ((ultraviolet or uv) with (neon)) same</pre>	HODAM	0000/00/45 40 50
	203	(inert or Ar or argon)	USPAT; US-PGPUB;	2003/02/15 10:12
		(india of the or digotty	EPO; JPO;	1
			IBM TDB	
-	51	((((resist or photoresist or	USPĀT;	2003/01/31 15:49
		photopolymer\$7) near3 (develop\$3)) with	US-PGPUB;	
		(ultraviolet or uv)) and ((Si or silicon or silicone) with (cross adj link\$3 or	EPO; JPO;	
}		cur\$3 or harden\$3))) and etch\$3	IBM_TDB	
-	1644	(resist or photoresist or photopolymer\$7)	USPAT;	2003/01/31 17:12
		and ((develop\$3) adj20 (ultraviolet or	US-PGPUB;	2000,01,01 17.12
		uv))	EPO; JPO;	
_	84	//Si or silicon or silicon \	IBM_TDB	0000/01/55
	04	((Si or silicon or silicone) with (cross adj link\$3 or cur\$3 or harden\$3)) and	USPAT; US-PGPUB;	2003/01/31 17:14
		((resist or photoresist or photopolymer\$7)	EPO; JPO;	
		and ((develop\$3) adj20 (ultraviolet or	IBM TDB	
	500	uv)))		
-	583	430/328.ccls.	USPAT;	2003/02/01 14:11
			US-PGPUB;	
	ł		EPO; JPO; IBM TDB	
-	16	430/313.cor. and 430/328.cxr.	USPAT;	2004/01/09 16:55
			US-PGPUB;	
			EPO; JPO;	
_	101	(nost add (owness on development))	IBM_TDB	
	181	(post adj (expos\$ or develop\$4)) adj20 (ultraviolet or uv)	USPAT;	2003/01/31 18:11
		(azeravioree or av)	US-PGPUB; EPO; JPO;	
	ĺ	ļ	IBM TDB	
-   f	49	((post adj (expos\$ or develop\$4)) adj20	USPAT;	2003/01/31 18:14
		(ultraviolet or uv)) and ((Si or silicon	US-PGPUB;	
		or silicone) with (polymer\$7 or	EPO; JPO;	
		<pre>photopolymer\$7 or photoresist or resist))</pre>	IBM_TDB	

-				
_	21	<pre>(((post adj (expos\$ or develop\$4)) adj20 (ultraviolet or uv)) and ((Si or silicon or silicone) with (polymer\$7 or photopolymer\$7 or photoresist or resist))) not ((silicon or Si) near3 (wafer or</pre>	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/01/31 18:30
-	15	substrate)) ((((post adj (expos\$ or develop\$4)) adj20 (ultraviolet or uv)) and ((Si or silicon or silicone) with (polymer\$7 or	USPAT; US-PGPUB; EPO; JPO;	2004/01/09 16:56
_	9	<pre>photopolymer\$7 or photoresist or resist))) not ((silicon or Si) near3 (wafer or substrate))) and etch\$3 ("4751170"   "4931351"   "5407786"  </pre>	IBM_TDB	2003/02/01 10:33
		"5427649"   "5486424"   "5688723"   "5707783"   "5877075"   "6190837").PN.	OSFAI	2003/02/01 10:33
_	567	430/328.ccls. not 430/313.cor.	USPAT; US-PGPUB; EPO; JPO;	2003/02/01 14:36
-	1	(((ultraviolet or uv) with (neon)) and ((cross adj link\$3 or cur\$3 or harden\$3) with (polymer\$7 or photopolymer\$7 or	IBM_TDB USPAT; US-PGPUB; EPO; JPO;	2004/01/09 16:57
_	12	photoresist or resist))) and ((Ar or argon or inert) with (flow or flowrate or rate)) (430/328.ccls. not 430/313.cor.) and ((Ar or argon or inert) with (flow or flowrate or rate))	IBM_TDB  USPAT; US-PGPUB; EPO; JPO;	2004/01/09 16:58
-	11	((430/328.ccls. not 430/313.cor.) and ((Ar or argon or inert) same (flow or flowrate or rate))) not ((430/328.ccls. not	IBM_TDB USPAT; US-PGPUB; EPO; JPO;	2003/08/21 14:46
-	1	430/313.cor.) and ((Ar or argon or inert) with (flow or flowrate or rate))) ((430/328.ccls. not 430/313.cor.) and (((Ar or argon) and (Ne or neon)) same (flow or flowrate or rate or sccm or	IBM_TDB  USPAT; US-PGPUB; EPO; JPO;	2004/01/09 16:58
-	329	slm))) not ((430/328.ccls. not 430/313.cor.) and ((Ar or argon or inert) with (flow or flowrate or rate))) ((resist or photoresist or photopolymer\$7) and (((Ar or argon) and (Ne or neon)) same	<pre>IBM_TDB  USPAT; US-PGPUB;</pre>	2003/02/01 15:31
_	66	<pre>(flow or flowrate or rate or sccm or slm))) not ((430/328.ccls. not 430/313.cor.) and ((Ar or argon or inert) with (flow or flowrate or rate))) ((resist or photoresist or photopolymer\$7)</pre>	EPO; JPO; IBM_TDB USPAT;	2003/02/01 16:50
		and (((Ar or argon) and (Ne or neon)) with (flow or flowrate or rate or sccm or slm))) not ((430/328.ccls. not 430/313.cor.) and ((Ar or argon or inert)	US-PGPUB; EPO; JPO; IBM_TDB	2003/02/01 16:50
-	15	with (flow or flowrate or rate))) ((resist or photoresist or photopolymer\$7) and (((Ar or argon) and (Ne or neon)) with (flow or flowrate or rate or sccm or slm)) same etch\$3) not ((430/328.ccls. not 430/313.cor.) and ((Ar or argon or inert)	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2004/01/09 16:59
-	51	<pre>with (flow or flowrate or rate))) (((resist or photoresist or photopolymer\$7) and (((Ar or argon) and</pre>	USPAT; US-PGPUB;	2004/01/09 16:59
		(Ne or neon)) with (flow or flowrate or rate or sccm or slm))) not ((430/328.ccls. not 430/313.cor.) and ((Ar or argon or inert) with (flow or flowrate or rate)))) not (((resist or photoresist or photopolymer\$7) and (((Ar or argon) and (Ne or neon)) with (flow or flowrate or rate or sccm or slm)) same etch\$3) not ((430/328.ccls. not 430/313.cor.) and ((Ar	EPO; JPO; IBM_TDB	
		or argon or inert) with (flow or flowrate or rate))))		

		(420/220 gglg+ 420/212	T-70	
	554	(430/328.ccls. not 430/313.cor.) not ((((ultraviolet or uv) with (neon)) and ((cross adj link\$3 or cur\$3 or harden\$3) with (polymer\$7 or photopolymer\$7 or photoresist or resist))) and ((Ar or argon or inert) with (flow or flowrate or rate))) not ((430/328.ccls. not 430/313.cor.) and ((Ar or argon or inert) with (flow or flowrate or rate))) not (((430/328.ccls. not 430/313.cor.) and (((Ar or argon) and (Ne or neon)) same (flow or flowrate or rate or sccm or slm))) not ((430/328.ccls. not 430/313.cor.) and ((Ar or argon or inert) with (flow or flowrate or rate)))) not (((resist or photoresist or photopolymer\$7) and (((Ar or argon) and (Ne or neon)) with (flow or flowrate or rate or sccm or slm)) same etch\$3) not ((430/328.ccls. not 430/313.cor.) and ((Ar or argon or inert) with (flow or flowrate or rate)))) not (((resist or photopolymer\$7) and (((Ar or argon) and (Ne or neon)) with (flow or flowrate or rate)))) not (((resist or photopolymer\$7) and ((Ar or argon) and (Ne or neon)) with (flow or flowrate or rate or sccm or slm))) not ((430/328.ccls. not 430/313.cor.) and ((Ar or argon or inert) with (flow or flowrate or rate or sccm or slm))) not (((resist or photoresist or photopolymer\$7) and (((Ar or argon) and (Ne or neon)) with (flow or flowrate or rate)))) not (((resist or photoresist or photopolymer\$7) and (((Ar or argon) and (Ne or neon)) with (flow or flowrate or rate)))) not (((resist or photoresist or photopolymer\$7) and (((Ar or argon) and (Ne or neon)) with (flow or flowrate or rate)))) not (((resist or photoresist or photopolymer\$7) and (((Ar or argon) and (Ne or neon)) with (flow or flowrate or rate)))) not (((resist or photoresist or photopolymer\$7) and (((Ar or argon) and (Ne or neon)) with (flow or flowrate or rate)))) not (((resist or photoresist or photopolymer\$7) and ((Ar or argon) and (Ne or neon)) with (flow or flowrate or rate)))	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/08/21 15:11
		((430/328.ccls. not 430/313.cor.) and ((Ar		
		or argon or inert) with (flow or flowrate or rate)))))		
_	1984	430/313,317.ccls. not (430/328.ccls. not 430/313.cor.)	USPAT; US-PGPUB; EPO; JPO; IBM TDB	2003/08/21 15:39
_	1	<pre>(((((resist or photoresist or photopolymer\$7) near3 (develop\$3)) with (ultraviolet or uv)) and ((Si or silicon or silicone) with (cross adj link\$3 or cur\$3 or harden\$3))) and etch\$3) and (Ne)</pre>	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2004/01/09 16:59
-	1	(((((resist or photoresist or photopolymer\$7) near3 (develop\$3)) with (ultraviolet or uv)) and ((Si or silicon or silicone) with (cross adj link\$3 or cur\$3 or harden\$3))) and etch\$3) and neon	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2004/01/09 17:01
ine	304	(ultraviolet or uv) with (Ne)	USPAT; US-PGPUB; EPO; JPO;	2003/02/15 10:10
_	0	<pre>(((ultraviolet or uv) with (Ne)) and ((cross adj link\$3 or cur\$3 or harden\$3) with (polymer\$7 or photopolymer\$7 or photoresist or resist))) and (neon same (flow or flowrate))</pre>	IBM_TDB USPAT; US-PGPUB; ÉPO; JPO; IBM_TDB	2003/08/21 15:45
	83	((ultraviolet or uv) with (Ne)) same (inert or Ar or argon)	USPAT; US-PGPUB; EPO; JPO; IBM TDB	2003/08/21 15:46
-	3	<pre>(((ultraviolet or uv) with (Ne)) and ((cross adj link\$3 or cur\$3 or harden\$3) with (polymer\$7 or photopolymer\$7 or photoresist or resist))) and ((Ar or argon or inert) with (flow or flowrate or rate))</pre>	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/08/21 15:55
-	1	("6054379").PN.	USPAT; US-PGPUB	2003/02/21 17:30

-	58	((ultraviolet or uv) with (Ne)) and ((cross adj link\$3 or cur\$3 or harden\$3) with (polymer\$7 or photopolymer\$7 or	USPAT; US-PGPUB; EPO; JPO;	2003/08/21 15:58
_	3	photoresist or resist))	IBM_TDB USPAT;	2003/08/21 16:06
			US-PGPUB; EPO; JPO; IBM_TDB	
_	143	430/313,317.ccls. and (etch\$3 with chamber) not (430/328.ccls. not 430/313.cor.)	USPAT; US-PGPUB; EPO; JPO;	2003/02/22 17:13
_	101	430/313,317.ccls. and (etch\$3 near3 chamber) not (430/328.ccls. not 430/313.cor.)	IBM_TDB USPAT; US-PGPUB; EPO; JPO;	2003/02/22 17:19
-	2231	(resist or photoresist) same ((ultraviolet or uv) with etch\$3)	IBM_TDB USPAT; US-PGPUB; EPO; JPO;	2003/02/22 17:23
_	175	((resist or photoresist) same ((ultraviolet or uv) with etch\$3)) and 430/313,317,328.ccls.	IBM_TDB USPAT; US-PGPUB; EPO; JPO; IBM TDB	2003/02/22 17:22
-	.17	(resist or photoresist) same ((ultraviolet or uv) with etch\$3 near2 chamber)	USPAT; US-PGPUB; EPO; JPO; IBM TDB	2003/02/22 17:23
_	4	250/504R-504H.ccls. and (neon or Ne) with (ultraviolet or uv)	USPAT;	2003/08/21 16:07
-	2	(((ultraviolet or uv) with (neon)) and ((cross adj link\$3 or cur\$3 or harden\$3) with (polymer\$7 or photopolymer\$7 or	US-PGPUB USPAT; US-PGPUB; EPO; JPO;	2004/01/09 17:03
-	21	photoresist or resist))) and (neon same (flow or flowrate)) 430/313.cor. and 430/328.cxr.	IBM_TDB  USPAT; US-PGPUB;	2004/01/09 17:04
			EPO; JPO; IBM TDB	
	16	<pre>((((post adj (expos\$ or develop\$4)) adj20 (ultraviolet or uv)) and ((Si or silicon or silicone) with (polymer\$7 or photopolymer\$7 or photoresist or resist))) not ((silicon or Si) near3 (wafer or</pre>	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2004/01/09 17:06
-	3	substrate))) and etch\$3 (((ultraviolet or uv) with (neon)) and ((cross adj link\$3 or cur\$3 or harden\$3) with (polymer\$7 or photopolymer\$7 or photoresist or resist))) and ((Ar or argon	USPAT; US-PGPUB; EPO; JPO; IBM TDB	2004/01/09 17:07
-	0	or inert) with (flow or flowrate or rate)) (430/328.ccls. not 430/313.cor.) and ((Ar or argon or inert) with (flow or flowrate or rate))	USPAT; US-PGPUB; EPO; JPO;	2004/01/09 17:08
_	11	((430/328.ccls. not 430/313.cor.) and ((Ar or argon or inert) same (flow or flowrate or rate))) not ((430/328.ccls. not 430/313.cor.) and ((Ar or argon or inert)	IBM_TDB USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2004/01/09 17:09
_	1	with (flow or flowrate or rate))) ((430/328.ccls. not 430/313.cor.) and (((Ar or argon) and (Ne or neon)) same (flow or flowrate or rate or sccm or slm))) not ((430/328.ccls. not 430/313.cor.) and ((Ar or argon or inert)	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2004/01/09 17:10
_	20	with (flow or flowrate or rate)) ((resist or photoresist or photopolymer\$7) and (((Ar or argon) and (Ne or neon)) with (flow or flowrate or rate or sccm or slm)) same etch\$3) not ((430/328.ccls. not 430/313.cor.) and ((Ar or argon or inert) with (flow or flowrate or rate)))	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2004/01/09 17:10

	0	(((resist or photoresist or photopolymer\$7) and (((Ar or argon) and (Ne or neon)) with (flow or flowrate or rate or sccm or slm))) not ((430/328.ccls. not 430/313.cor.) and ((Ar or argon or inert) with (flow or flowrate or rate)))) not (((resist or photoresist or photopolymer\$7) and ((Ar or argon) and (Ne or neon)) with (flow or flowrate or rate or sccm or slm)) same etch\$3) not ((430/328.ccls. not 430/313.cor.) and ((Ar or argon or inert) with (flow or flowrate or rate)))	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2004/01/09 17:11
	586	(430/328.ccls. not 430/313.cor.) not ((((ultraviolet or uv) with (neon)) and ((cross adj link\$3 or cur\$3 or harden\$3) with (polymer\$7 or photopolymer\$7 or photoresist or resist))) and ((Ar or argon or inert) with (flow or flowrate or rate))) not ((430/328.ccls. not .430/313.cor.) and ((Ar or argon or inert) with (flow or flowrate or rate))) not (((430/328.ccls. not 430/313.cor.) and (((Ar or argon) and (Ne or neon)) same (flow or flowrate or rate or sccm or slm))) not ((430/328.ccls. not .430/313.cor.) and ((Ar or argon or inert) with (flow or flowrate or rate)))) not (((resist or photoresist or photopolymer\$7) and (((Ar or argon) and (Ne or neon)) with (flow or flowrate or rate or sccm or slm)) same etch\$3) not ((430/328.ccls. not 430/313.cor.) and ((Ar or argon or inert) with (flow or flowrate or rate)))) not ((((resist or photoresist or photopolymer\$7) and (((Ar or argon) and (Ne or neon)) with (flow or flowrate or rate or sccm or slm))) not ((430/328.ccls. not 430/313.cor.) and ((Ar or argon or inert) with (flow or flowrate or rate or sccm or slm))) not (((resist or photopolymer\$7) and (((Ar or argon) and (Ne or neon)) with (flow or flowrate or rate or sccm or slm)) same etch\$3) not ((430/328.ccls. not 430/313.cor.) and ((Ar or argon or inert) with (flow or flowrate or rate or sccm or slm)) same etch\$3) not ((430/328.ccls. not 430/313.cor.) and ((Ar or argon or inert) with (flow or flowrate	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2004/01/09 17:12
_	377	or argon or inert) with (flow or flowrate or rate))))) 430/313,317.ccls. not (430/328.ccls. not 430/313.cor.)	USPAT; US-PGPUB;	2004/01/09 17:13
-	1	(((((resist or photoresist or photopolymer\$7) near3 (develop\$3)) with (ultraviolet or uv)) and ((Si or silicon or silicone) with (cross adj link\$3 or	EPO; JPO; IBM_TDB USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2004/01/09 17:19
	1	cur\$3 or harden\$3))) and etch\$3) and (Ne) (((((resist or photoresist or photopolymer\$7) near3 (develop\$3)) with (ultraviolet or uv)) and ((Si or silicon or silicone) with (cross adj link\$3 or	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2004/01/09 17:20
_	0	<pre>cur\$3 or harden\$3))) and etch\$3) and neon (((ultraviolet or uv) with (Ne)) and ((cross adj link\$3 or cur\$3 or harden\$3) with (polymer\$7 or photopolymer\$7 or photoresist or resist))) and (neon same (flow or flowrate))</pre>	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2004/01/09 17:20
-	102	((ultraviolet or uv) with (Ne)) same (inert or Ar or argon)	USPAT; US-PGPUB; EPO; JPO; IBM TDB	2004/01/09 17:21

-	4	<pre>(((ultraviolet or uv) with (Ne)) and ((cross adj link\$3 or cur\$3 or harden\$3) with (polymer\$7 or photopolymer\$7 or photoresist or resist))) and ((Ar or argon or inert) with (flow or flowrate or rate))</pre>	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2004/01/09 17:21
_	71	((ultraviolet or uv) with (Ne)) and ((cross adj link\$3 or cur\$3 or harden\$3) with (polymer\$7 or photopolymer\$7 or photoresist or resist))	USPAT; US-PGPUB; EPO; JPO; IBM TDB	2004/01/09 17:22
_	4	430/313.cor. and 430/328.cxr. and (etch\$3 with chamber)	USPAT; US-PGPUB; EPO; JPO; IBM TDB	2004/01/09 17:23
-	4	250/504R-504H.ccls. and (neon or Ne) with (ultraviolet or uv)	USPAT; US-PGPUB; EPO; JPO; IBM TDB	2004/01/09 17:23
-	2	<pre>(((ultraviolet or uv) with (neon)) and ((cross adj link\$3 or cur\$3 or harden\$3) with (polymer\$7 or photopolymer\$7 or photoresist or resist))) and (neon same (flow or flowrate))</pre>	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2004/01/09 16:55
-	25	430/313.cor. and 430/328.cxr.	USPAT; US-PGPUB; EPO; JPO; IBM TDB	2004/01/09 16:55
-	16	<pre>((((post adj (expos\$ or develop\$4)) adj20 (ultraviolet or uv)) and ((Si or silicon or silicone) with (polymer\$7 or photopolymer\$7 or photoresist or resist))) not ((silicon or Si) near3 (wafer or substrate))) and etch\$3</pre>	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2004/01/09 16:57
-	3	<pre>(((ultraviolet or uv) with (neon)) and ((cross adj link\$3 or cur\$3 or harden\$3) with (polymer\$7 or photopolymer\$7 or photoresist or resist))) and ((Ar or argon or inert) with (flow or flowrate or rate))</pre>	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2004/01/09 16:57
_	14	(430/328.ccls. not 430/313.cor.) and ((Ar or argon or inert) with (flow or flowrate or rate))	USPAT; US-PGPUB; EPO; JPO; IBM TDB	2004/01/09 16:58
-	2	((430/328.ccls. not 430/313.cor.) and (((Ar or argon) and (Ne or neon)) same (flow or flowrate or rate or sccm or slm))) not ((430/328.ccls. not 430/313.cor.) and ((Ar or argon or inert) with (flow or flowrate or rate)))	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2004/01/09 16:58
	23	((resist or photoresist or photopolymer\$7) and (((Ar or argon) and (Ne or neon)) with (flow or flowrate or rate or sccm or slm)) same etch\$3) not ((430/328.ccls. not 430/313.cor.) and ((Ar or argon or inert) with (flow or flowrate or rate)))	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2004/01/10 15:59
	76	(((resist or photoresist or photopolymer\$7) and (((Ar or argon) and (Ne or neon)) with (flow or flowrate or rate or sccm or slm))) not ((430/328.ccls. not 430/313.cor.) and ((Ar or argon or inert) with (flow or flowrate or rate)))) not (((resist or photoresist or photopolymer\$7) and (((Ar or argon) and (Ne or neon)) with (flow or flowrate or rate or sccm or slm)) same etch\$3) not ((430/328.ccls. not 430/313.cor.) and ((Ar	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2004/01/09 16:59
-	1	or argon or inert) with (flow or flowrate or rate)))) (((((resist or photoresist or photopolymer\$7) near3 (develop\$3)) with (ultraviolet or uv)) and ((Si or silicon or silicone) with (cross adj link\$3 or cur\$3 or harden\$3))) and etch\$3) and (Ne)	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2004/01/09 17:00

-	1	(((((resist or photoresist or	USPAT;	2004/01/09 17:01
		photopolymer\$7) near3 (develop\$3)) with	US-PGPUB;	
		(ultraviolet or uv)) and ((Si or silicon	EPO; JPO;	
		or silicone) with (cross adj link\$3 or cur\$3 or harden\$3))) and etch\$3) and neon	IBM_TDB	
_	2	(((ultraviolet or uv) with (neon)) and	IICDAM.	2004/01/00 17 02
		((cross adj link\$3 or cur\$3 or harden\$3)	USPAT;	2004/01/09 17:03
		with (polymer\$7 or photopolymer\$7 or	US-PGPUB;	
		photoresist or resist))) and (neon same	EPO; JPO; IBM TDB	
		(flow or flowrate))	100-100	
_	21		USPAT;	2004/01/09 17:04
		with chamber)	US-PGPUB;	2004/01/09 17:04
			EPO; JPO;	
			IBM TDB	
_	16	((((post adj (expos\$ or develop\$4)) adj20	USPAT;	2004/01/09 17:06
		(ultraviolet or uv)) and ((Si or silicon	US-PGPUB;	2001,01,03 1,100
		or silicone) with (polymer\$7 or	EPO; JPO;	
		<pre>photopolymer\$7 or photoresist or resist)))</pre>	IBM TDB	
		not ((silicon or Si) near3 (wafer or	_	
	j	substrate))) and etch\$3		
-	3	(((ultraviolet or uv) with (neon)) and	USPAT;	2004/01/09 17:07
		((cross adj link\$3 or cur\$3 or harden\$3)	US-PGPUB;	
		with (polymer\$7 or photopolymer\$7 or	EPO; JPO;	
		photoresist or resist))) and ((Ar or argon	IBM_TDB	
		or inert) with (flow or flowrate or rate))		
_	14	(430/328.ccls. not 430/313.cor.) and ((Ar	USPAT;	2004/01/09 17:08
		or argon or inert) with (flow or flowrate	US-PGPUB;	
		or rate))	EPO; JPO;	
	12	///20/220 0010 004 /20/212 \ \ //2	IBM_TDB	
-	12	((430/328.ccls. not 430/313.cor.) and ((Ar	USPAT;	2004/01/09 17:09
		or argon or inert) same (flow or flowrate or rate))) not ((430/328.ccls. not	US-PGPUB;	
		430/313.cor.) and ((Ar or argon or inert)	EPO; JPO;	
		with (flow or flowrate or rate)))	IBM_TDB	
_	2	((430/328.ccls. not 430/313.cor.) and	USPAT;	2004/01/09 17:10
	-	(((Ar or argon) and (Ne or neon)) same	US-PGPUB;	2004/01/09 17:10
		(flow or flowrate or rate or sccm or	EPO; JPO;	1
		slm))) not ((430/328.ccls. not	IBM TDB	
		430/313.cor.) and ((Ar or argon or inert)	1511_155	
		with (flow or flowrate or rate)))		
_	23	((resist or photoresist or photopolymer\$7)	USPAT;	2004/01/09 17:10
		and (((Ar or argon) and (Ne or neon)) with	US-PGPUB;	
		(flow or flowrate or rate or sccm or slm))	EPO; JPO;	
		same etch\$3) not ((430/328.ccls. not	IBM_TDB	
		430/313.cor.) and ((Ar or argon or inert)	•	
		with (flow or flowrate or rate)))		
-	76	(((resist or photoresist or	USPAT;	2004/01/09 17:11
		photopolymer\$7) and (((Ar or argon) and	US-PGPUB;	
		(Ne or neon)) with (flow or flowrate or	EPO; JPO;	
		rate or sccm or slm))) not ((430/328.ccls.	IBM_TDB	
		not 430/313.cor.) and ((Ar or argon or		
		<pre>inert) with (flow or flowrate or rate)))) not (((regist or photograph)</pre>		
		not (((resist or photoresist or photopolymer\$7) and (((Ar or argon) and		
		(Ne or neon)) with (flow or flowrate or		
		rate or sccm or slm)) same etch\$3) not		
		((430/328.ccls. not 430/313.cor.) and ((Ar		
	1	or argon or inert) with (flow or flowrate		
		or rate))))		

	608	(430/328.ccls. not 430/313.cor.) not	HCDAM.	2004/01/00 17 10
	008	((((ultraviolet or uv) with (neon)) and	USPAT; US-PGPUB;	2004/01/09 17:12
		((cross adj link\$3 or cur\$3 or harden\$3)	EPO; JPO;	
		with (polymer\$7 or photopolymer\$7 or	IBM TDB	
		photoresist or resist))) and ((Ar or argon	_	
		or inert) with (flow or flowrate or		
		rate))) not ((430/328.ccls. not		
		430/313.cor.) and ((Ar or argon or inert) with (flow or flowrate or rate))) not		
		(((430/328.ccls. not 430/313.cor.) and		
		(((Ar or argon) and (Ne or neon)) same		
		(flow or flowrate or rate or sccm or		ļ
		slm))) not ((430/328.ccls. not		
		430/313.cor.) and ((Ar or argon or inert)		-
		<pre>with (flow or flowrate or rate)))) not (((resist or photoresist or</pre>		
		photopolymer\$7) and (((Ar or argon) and		
		(Ne or neon)) with (flow or flowrate or		
		rate or sccm or slm)) same etch\$3) not		
		((430/328.ccls. not 430/313.cor.) and ((Ar		
		or argon or inert) with (flow or flowrate		
		or rate)))) not ((((resist or photoresist or photopolymer\$7) and (((Ar or argon) and		
	İ	(Ne or neon)) with (flow or flowrate or		
		rate or sccm or slm))) not ((430/328.ccls.	1 .	
		not 430/313.cor.) and ((Ar or argon or		
		<pre>inert) with (flow or flowrate or rate))))</pre>		
		not (((resist or photoresist or		
		photopolymer\$7) and (((Ar or argon) and (Ne or neon)) with (flow or flowrate or		
İ		rate or sccm or slm)) same etch\$3) not		
		((430/328.ccls. not 430/313.cor.) and ((Ar		
		or argon or inert) with (flow or flowrate		
	1	or rate()))))		
-	1	(((((resist or photoresist or photopolymer\$7) near3 (develop\$3)) with	USPAT;	2004/01/09 17:19
		(ultraviolet or uv)) and ((Si or silicon	US-PGPUB; EPO; JPO;	
		or silicone) with (cross adj link\$3 or	IBM TDB	
		cur\$3 or harden\$3))) and etch\$3) and (Ne)	1007_100	
_	1	( ( ( ( = = = = = = = = = = = = = = = =	USPAT;	2004/01/09 17:20
		photopolymer\$7) near3 (develop\$3)) with	US-PGPUB;	
		(ultraviolet or uv)) and ((Si or silicon or silicone) with (cross adj link\$3 or	EPO; JPO;	
		cur\$3 or harden\$3))) and etch\$3) and neon	IBM_TDB	ļ
-	0	(((ultraviolet or uv) with (Ne)) and	USPAT;	2004/01/09 17:20
		((cross adj link\$3 or cur\$3 or harden\$3)	US-PGPUB;	
		with (polymer\$7 or photopolymer\$7 or	EPO; JPO;	
		photoresist or resist))) and (neon same	IBM_TDB	
_	115	<pre>(flow or flowrate)) ((ultraviolet or uv) with (Ne)) same</pre>	IIGDAM.	2004/01/00 17 01
		(inert or Ar or argon)	USPAT; US-PGPUB;	2004/01/09 17:21
		9,	EPO; JPO;	
			IBM_TDB	
-	5	(((ultraviolet or uv) with (Ne)) and	USPĀT;	2004/01/09 17:22
		((cross adj link\$3 or cur\$3 or harden\$3)	US-PGPUB;	
		with (polymer\$7 or photopolymer\$7 or photoresist or resist))) and ((Ar or argon	EPO; JPO;	
		or inert) with (flow or flowrate or rate))	IBM_TDB	
-	74	((ultraviolet or uv) with (Ne)) and	USPAT;	2004/01/09 17:22
		((cross adj link\$3 or cur\$3 or harden\$3)	US-PGPUB;	1,.22
		with (polymer\$7 or photopolymer\$7 or	EPO; JPO;	
! _	4	photoresist or resist))	IBM_TDB	0004/05/55
_	4	430/313.cor. and 430/328.cxr. and (etch\$3 with chamber)	USPAT;	2004/01/09 17:23
		wren cuammer)	US-PGPUB; EPO; JPO;	
	[		IBM TDB	
-	4	250/504R-504H.ccls. and (neon or Ne) with	USPAT;	2004/01/09 17:23
	ļ l	(ultraviolet or uv)	US-PGPUB;	, == =
			EPO; JPO;	
L			IBM_TDB	

-	17	430/328.ccls. and (uv or ultraviolet or	USPAT;	2004/01/10 17:06
		ultra adj violet) same (temperature or	US-PGPUB;	
		\$4"degree") same plasma	EPO; JPO;	
			IBM TDB	
-	145	430/328.ccls. and (uv or ultraviolet or	USPAT;	2004/01/10 17:08
		ultra adj violet) same (temperature or	US-PGPUB;	
		\$4"degree") not plasma	EPO; JPO;	
			IBM TDB	
_	41	430/313.ccls. and (uv or ultraviolet or	USPAT;	2004/01/10 16:52
		ultra adj violet) same (\$4"degree") same	US-PGPUB;	
		plasma not 430/328.ccls.	EPO; JPO;	
			IBM TDB	
_	342	(	USPAT;	2004/01/10 19:10
		ultraviolet or ultra adj violet) same	US-PGPUB;	
		(\$4"degree") same plasma	EPO; JPO;	
	_		IBM_TDB	
_	22	250/504R-504H.ccls. and plasma and (uv or	USPAT;	2004/01/10 19:15
		ultraviolet or ultra adj violet) same	US-PGPUB;	İ
		(\$4"degree")	EPO; JPO;	
	L.,	VALUE OF THE PROPERTY OF THE P	IBM TDB	